Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	719	kanayama-t$.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 12:51
L2	130	kouno-h$.in.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 12:51
L3	845	l1 or l2	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 12:52
L4	412	("xeF2" or "xeF.sub.2") with (vapor or vapour or gas)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:42
L6	412	("xeF2" or "xeF.sub.2") with (vapor or vapour or vapourous or vaporous or gas)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:16
L7	412	("xeF2" or "xeF.sub.2") with (vapor or vapour or vapourous or vaporous or gas or mist)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:03

L11	718271	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or contact or contacting or contacted or strip or stripping or stripped or stripper or etch or etchant or etching or etched) adj10 (chamber or vessel or reactor or tank or container or equipment or machinery or apparatus or ((chemical adj3 vapor adj3 deposition or vapor adj3 deposition or deposition or chemical adj3 vapor or process or processing) adj5 (reactor or chamber or vessel or tank or container)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:10
L12	113856	(immerse or immersing or immersed or immersion or soak or soaking or soaked or degrease or degreasing or degreaser or degreased or flush or flushing or flushed or purge or purged or purging) adj10 (chamber or vessel or reactor or tank or container or equipment or machinery or apparatus or ((chemical adj3 vapor adj3 deposition or vapor adj3 deposition or deposition or chemical adj3 vapor or process or processing) adj5 (reactor or chamber or vessel or tank or container)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:11
L13	583901	(clean or cleaning or cleaned or cleaner or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or contact or contacting or contacted or strip or stripping or stripped or stripper or etch or etchant or etching or etched or decontaminate or decontaminated or decontaminating or decontaminated or purge or purging or purged or flush or flushing or flushed) adj10 (article or substrate or silicon or wafer or semiconductor or workpiece)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:14

L14	2025	(degrease or degreasing or degreased or degreaser) adj10 (article or substrate or silicon or wafer or semiconductor or workpiece)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:15
L15	584577	l13 or l14	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:15
L16	795322	l11 or l12	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:15
L17	1281909	l15 or l16	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:15
L18	191	l17 same l7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:20
L19	223074	("134"/$ OR "216"/$ OR "438"/$).CCLS.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:21
L20	89	L18 AND L19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:21
L21	984	("xeF2" or "xeF.sub.2" or xenon adj3 difluoride or "XeF.sub.2" or "XeF2")	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:50

L22	87317	(dry-clean$3 or dry adj3 clean$3 or dry-etch$4 or dry adj3 etch$4)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:45
L23	343	l22 and l21	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:09
L24	165	l17 and l23 and l19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:09
L25	2	l24 and l3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 13:47
L26	196	l22 same l21	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:09
L27	74	l17 and l26 and l19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:16
L28	4	l3 and l7	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:17
L29	812279	(remove or removing or removed or removal) adj10 (oil or oily or fat or fatty or residue or residual or soil or foreign adj3 matter or contaminant or contamination or impurity or particle or particulate or film or layer or photoresist or resist or grease or greasy)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:19

L30	1496884	(eliminate or eliminating or eliminated or elimination or strip or stripping or stripped or stripper or etch or etching or etched or etchant or clean or cleaning or cleaned or cleanse or cleansing or cleansed or cleanser or treat or treating or treated or treatment or wash or washing or washed or dissolve or dissolving or dissolved or dissolution or decontaminate or decontaminating or decontaminated or decontamination or flush or flushing or flushed or immerse or immersing or immersed or immersion or contact or contacted or contacting) adj10 (oil or oily or fat or fatty or residue or residual or soil or foreign adj3 matter or contaminant or contamination or impurity or particle or particulate or film or layer or photoresist or resist or grease or greasy)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:44
L31	1857058	I29 or I30	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:44
L32	110	("xeF2" or "xeF.sub.2" or xenon adj3 difluoride or "XeF.sub.2" or "XeF2") same (water or "H2O" or "H.sub.2O" or moisture or steam)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:53
L33	29	I31 same I32	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:55
L34	54	I31 and I32 and vacuum$	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:56
L35	17	I34 and I19	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2004/09/08 14:56